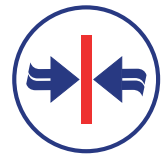
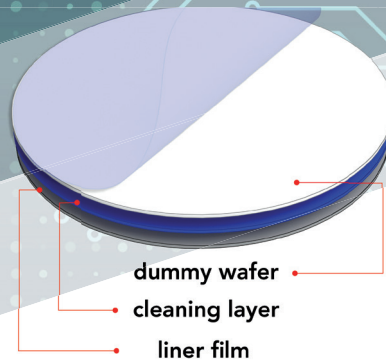


CLEANING WAFER™

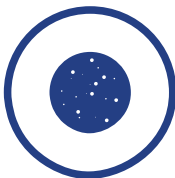
Wafer particle remover for continuous workflows



TO ADHERE

The Cleaning Wafer™ is a highly efficient particle remover featuring a cleaning layer allowing for a constant semiconductor production workflow. Down-time of tools can be drastically reduced compared to conventional hand cleaning. The Cleaning Wafer™ can also be used for

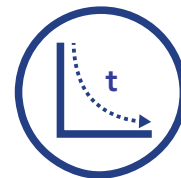
maintenance to improve long-term performance. Nitto's solution for clean wafers is applicable in vacuum chambers in semiconductor front-end and mid-end process of semiconductor manufacturing equipment.



highly efficient particle removal



enabling continuous workflows



reducing down-time of tools



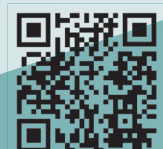
suitable for various applications



easy handling minimal stickiness

Nitto

Innovation for Customers



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